

Title (en)  
PROCESS FOR PRODUCING FLUORINE GAS

Title (de)  
VERFAHREN ZUR HERSTELLUNG VON FLUORGAS

Title (fr)  
PROCEDE DE PRODUCTION DE GAZ FLUORE

Publication  
**EP 1848662 A1 20071031 (EN)**

Application  
**EP 05787668 A 20050922**

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Abstract (en)  
[origin: WO2006033474A1] A process for producing a fluorine gas of the invention comprises a step (1) of generating a fluorine gas by sectioning the interior of a fluorine gas generation container equipped with a heating means, by the use of a structure having gas permeability, then filling each section with a high-valence metal fluoride and heating the high-valence metal fluoride. The process may comprise a step (2) of allowing the high-valence metal fluoride, from which a fluorine gas has been generated in the step (1), to occlude a fluorine gas. According to the process of the invention, a high-purity fluorine gas that is employable as an etching gas or a cleaning gas in the process for manufacturing semiconductors or liquid crystals can be produced inexpensively on a mass scale.

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